



The Fine Line : VIDEOS FOR THE EBEAM COMMUNITY

Autumn 2014

Shot Talk - A Word from our Sponsor

Shot Talk catches up with Aki Fujimura, CEO of D2S, who shares his thoughts on the key themes and hot topics at BACUS, including inevitability of complex mask shapes at the 10-nm node, new breakthroughs in multibeam mask writing, and the context dependent nature of sub-50-nm mask shapes.



VIDEO ARCHIVE

The Fine Line Summer 2014 Edition



Shot Talk: Aki Fujimura, D2S

From the White Board

Kang-Hoon Choi of Fraunhofer CNT explores the capabilities, limitations and requirements of corner rounding correction in mask data preparation to support writing smaller mask features with eBeam technology.



From the White Board:
Dr. David Lam, Multibeam Corp.

Tech Talk

[Aki Fujimura](#) teams up with [Bob Pack](#) of GLOBALFOUNDRIES in separate videos to explain how context-dependent mask effects require simulation-based MDP as well as describe a potential flow for integrated mask/lithography signoff verification to address mask hotspots.



Click [here](#) to watch Aki's video in Japanese.



Tech Talk: Tony Luo,
Maglen

Perspectives

Industry luminaries Tom Faure of IBM, Bob Pack of GLOBALFOUNDRIES, Noriaki Nakayama of NuFlare and Aki Fujimura share the stage at a panel event at BACUS to analyze the mask industry's responses to the latest eBeam Initiative survey.



Perspectives: Dr. Sergey Babin,
aBeam Technologies

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The eBeam Initiative provides a forum for educational and promotional activities regarding new semiconductor manufacturing approaches based on electron beam (eBeam) technologies. Its goals are to reduce the barriers to adoption to enable more integrated circuit (IC) design starts and faster time-to-market while increasing the investment in eBeam technologies throughout the semiconductor ecosystem. For more information, please e-mail requests@ebeam.org or visit www.ebeam.org